Carnegie Mellon

Pittsburgh, November 10, 2020

Dr. DerChang Kau,
Intel Fellow and Director, Optane Advanced Pathfinding,
Intel Optane Group
Intel Corporation

Dear DerChang:

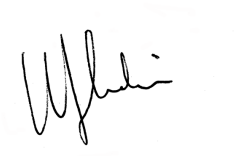
This is in response to your request for my assessment of Davide Fugazza concerning his promotion to Principal Engineer at Intel Corporation.

I have got to know Davide through his publications while at the Politecnico di Milano and, more importantly, through the interaction with him as a point of contact for the Intel project at Carnegie Mellon “Mass transport in chalcogenide alloys: driving forces pareto”. Davide was instrumental in shaping our proposal to align the technical thrusts with the interests of the Optane group. It is a difficult process of balancing the need for being technically relevant and at the same time focused on precompetitive fundamental phenomena. Davide was instrumental in this respect.

Even more important was the interaction during the actual work. The project was staffed by two first year students, Qiyun Xu (PhD) and Enkui Lian (MSc). Both were at the critical stage of their development as engineers having done with most of the classes and just starting at research. Davide served as a technical guide and a role model helping the students transform during this year from school students expecting to be told what’s next into budding researchers setting their own goals and finding creative solutions to problems. It took a combination of technical expertise, relentless pointing out the weaknesses, and availability at all times that amounted to Davide being perfect mentor. I personally benefitted from this interaction as well and was impressed by Davide’s professionality and technical excellence.

Clearly, I cannot comment on Davide’s leadership and accomplishments at Intel. Everything I have seen point to him richly deserving a promotion of principal Engineer.

Sincerely,



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